

VaporSorb™ CLR Chemical Filters

Cleanroom ceiling filtration solutions provide complete protection against the full range of airborne molecular contamination at 22 nm and below



The VaporSorb™ family of hybrid chemical air filters are designed to offer superior protection for advanced semiconductor manufacturing environments at sub-22 nm nodes. Entegris VaporSorb filters are laboratory and field proven for use in semiconductor manufacturing environments, including lithography, etch, CMP, metrology, and reticle storage areas.

Entegris VaporSorb CLR filters help reduce the levels of unwanted airborne molecular contamination (AMC) in the cleanroom, reducing tool filter exposure to excessive contamination levels, which extends tool filter service life. The VaporSorb filters also help reduce levels of regulated species to levels at or below those specified by tool OEMs.

The Entegris VaporSorb CLR filters are designed using our extensive database of cleanroom AMC concentrations to provide maximum effectiveness and contaminant removal.

FEATURES & BENEFITS

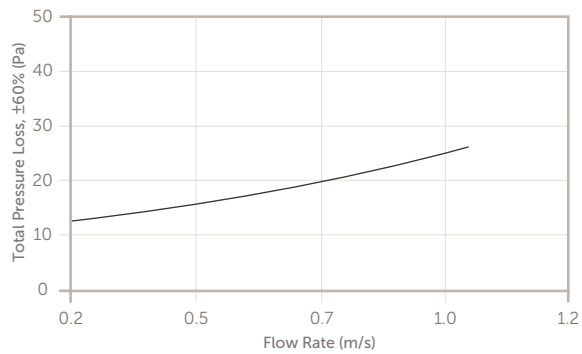
Full-range protection from weak acids, strong acids, organics, and bases such as ammonia	Decreases wafer defects and increases yields Improves equipment uptime
Application-specific filters with optimized blend of adsorbents	Targets and removes contaminants of concern for each process tool Minimizes media waste, lowering cost of ownership (COO)
Flexible configurations for any FFU, in-tool, equipment factory interface, or process module mounting	Simplifies installation and integration
Data-driven See it. Control it. methodology	AMC measurement provides tailored solutions that are optimized for customer fab environment Minimizes media waste, lowering COO
Entegris-owned filter manufacturing	Quick turnaround of fab-specific optimized media Minimizes media waste, lowering COO
Product backed by Entegris OEM-approved, ISO® 17025-accredited laboratories	Provides assurance that all filter performance claims are verified with supporting data

SPECIFICATIONS

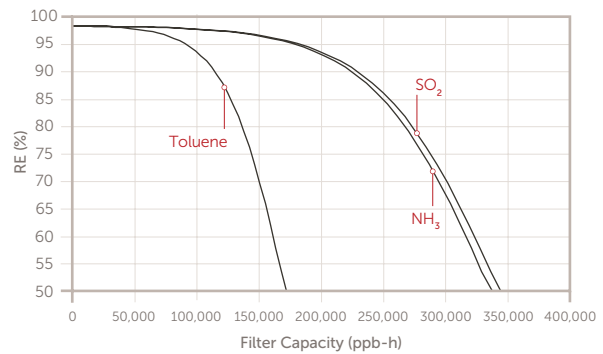
Nominal size	242412	241212
Targeted air flow	300 CFM	150 CFM
Targeted face velocity	0.4 m/s (75 ft/min)	0.4 m/s (75 ft/min)
Height	592 mm (23.312")	287 mm (11.312")
Width	592 mm (23.312")	592 mm (23.312")
Depth	287 mm (11.312")	287 mm (11.312")
Weight	14.5 kg (32 lbs)	9.1 kg (20 lbs)
Pressure drop	12 Pa @ 0.4 m/s (75 ft/min)	12 Pa @ 0.4 m/s (75 ft/min)

PERFORMANCE DATA

Pressure vs. Flow



Chemical Capacity*



*Entegris expresses filter AMC capacity as the product of challenge concentration and time, the unit is ppb-h (parts per billion-hours; ppb = 10⁻⁹ mols per mol of air). With that number, and the desired end-of-life removal efficiency, the user can calculate lifetime in hours by using their measured onsite AMC concentration.

FOR MORE INFORMATION

Please call your Regional Customer Service Center today to learn what Entegris can do for you. Visit entegris.com and select the [Contact Us](#) link to find the customer service center nearest you.

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